This Sheet Has Been Replaced



ABSTRACT OF THE DISCLOSURE (FIG. 2)

"PROCESSING SYSTEM"

A processing system comprises a plurality of types of internal processing machines (COT, DEV) that perform various processes on a semiconductor substrate and an interface section (13) that delivers and receives the semiconductor substrate to and from an external exposure machine (12) for performing an exposure process on the substrate subjected to a resist coating process, wherein the interface section includes a transfer unit (32) for taking in the substrate subjected to a specific process from at least one of the internal processing machines and transferring the substrate and a substrate table unit (33) for temporarily holding the substrate to transfer the substrate between the internal processing machine and the external exposure machine via the transfer unit. The substrate table unit has a first and second tables that are laid one on top of the other and can move up and down and stop at a specific height, the first table allowing the substrate to be temporarily placed on it in transferring the substrate to the external exposure machine, and the second table allowing the substrate to be temporarily placed on it in receiving the substrate from the external exposure machine. The transfer unit transfers the substrate between the first and second tables and at least one of the processing machines.